

REMARKS

In the Final Rejection, the Examiner rejects Claims 1-10, 12, 14, 16, 18, 20, 22, 24, 26, 28 and 30-32 under 35 USC §103 as being unpatentable over "applicant's admitted prior art in combination with Chen." This rejection is respectfully traversed.

In order to advance the prosecution of this application, Applicants have amended all of the independent claims herein to recite an EL layer and to add the feature of a leveling film containing a siloxane structure. This feature is described, for example, in the specification of the present application at page 7, ln. 10. Applicants have further amended independent Claim 6 to add the feature of a wiring over the gate wiring and to delete the limitation of that each of the first organic leveling film and the second organic leveling film comprises at least one of a polyimide resin and an acrylic resin, so there is no contradiction in the claims.

The claimed combination of a leveling film containing a siloxane structure and an EL layer is advantageous. For example, a relatively high temperature can be applied to a leveling film containing a siloxane structure as a baking process compared to using an acryl resin film, which is commonly used as a leveling film. Hence, the degassing of a leveling film containing a siloxane structure is less than that of an acryl resin film. Since an EL layer is easily damaged by moisture and oxygen (see e.g. page 21, lns. 14-15 of the specification), less degassing prolongs the EL layer and results in higher reliability of the display device. Another advantage of the claimed device is that transmittance of a leveling film containing a siloxane structure is higher than that of an acryl resin film. Therefore, the loss of light is smaller for a device having a leveling film containing a siloxane structure where the light emitted from the EL layer is filtered out from the leveling film.

The claimed method for fabricating a display device, as recited in the amended independent claims, is not disclosed or suggested by the cited references. For example, the cited references do not disclose or suggest forming a first leveling film containing a siloxane structure over the gate

wiring, and forming a second leveling film containing a siloxane structure on the first leveling film, as recited in the independent claims.

Therefore, the claims of the present application are patentable thereover. Accordingly, for at least the above-stated reasons, it is requested that the rejection of the claims of the present application be withdrawn.

Information Disclosure Statement

Applicants are including herewith an IDS. It is requested that this IDS be considered prior to any further action being issued on this application.

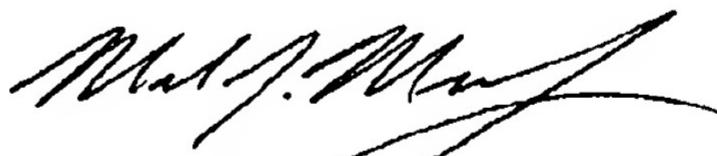
Conclusion

It is respectfully submitted that the present application is in a condition for allowance.

If any fee should be due for this amendment, please charge our deposit account 50/1039.

Favorable reconsideration is earnestly solicited.

Respectfully submitted,



Mark J. Murphy
Registration No. 34,225

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COOK, ALEX, McFARRON, MANZO,
CUMMINGS & MEHLER, Ltd.
200 West Adams Street, Suite 2850
Chicago, Illinois 60606
(312) 236-8500